

by liquid source misted chemical deposition (LSMCD) to the film-forming region having affinity to ceramics and the non-film-forming regions having no affinity to ceramics; and crystallizing the ceramic film by feeding an electromagnetic wave to the ceramic film.--

--53. The method of fabricating ceramics as defined in claim 52, further comprising feeding an active species of a substance which is part of raw materials for the ceramic film to the ceramic film in the step of forming the ceramic film or the step of crystallizing the ceramic film. --

--54. A method of forming ceramics, comprising:
forming a film-forming region having affinity to ceramics to be formed and a non-film-forming regions having no affinity to ceramics to be formed on a surface of a substrate;

forming a ceramic film in the film-forming region in a self-aligning way by feeding fine particles of a substance which is at least part of raw material for a ceramic film by liquid source misted chemical deposition (LSMCD) to the film-forming region having affinity to ceramics and the non-film-forming regions having no affinity to ceramics; and crystallizing the ceramic film by feeding an active species of a substance which is part of raw materials for the ceramic film to the ceramic film. --

--55. The method according to claim 54, further comprising crystallizing the ceramic film by feeding an electromagnetic wave to the ceramic film, in the step of forming the ceramic film or the step of crystallizing the ceramic film. --

--56. A ceramics fabrication device, comprising: